

Pan-American Advanced Studies Institute
(PASI)
in
Scalable, Functional Nanomaterials



Organized by

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in

Costa Rica
August 4th – 13th, 2011

Overview: The 10 day PASI program will consist of two sessions, each to be held at a separate location. From August 4th to 6th the PASI will be hosted by the National Center for High Technology (CeNAT) in the capital of San Jose. The PASI will then relocate to Punta Leona along the picturesque Pacific Coast of Costa Rica from August 7th to 12th (see online **Accommodations** page for details). After the conclusion of the PASI, a return to San Jose on August 13th/14th is scheduled to facilitate departures.

Who can apply: Graduate level, post-doctoral, and early-career scientists are encouraged to apply. Instructions and requirements can be found online at <http://www.jhuapl.edu/aboutapl/organization/MERC/pasi/Home.htm>. The application deadline is April 1, 2011. Applicants will be accepted based on the relevance of their research in relation to the PASI theme, as well as the strength of the recommendation letter. Students attending the PASI will be **supported** (airfare, lodging, most meals) through funds made available by the National Science Foundation.

About the PASI: There will be three types of organized scientific activities at the PASI, along with additional time for informal social interaction and scientific discussion. The main element of the PASI will be lectures given by the invited speakers. The lectures will focus on two main areas: scalable, bottom-up fabrication techniques to produce advanced nanomaterials and nanostructures, and the potential applications for such structures. There will also be student poster sessions in which the students present their own research. Finally, there will be planned hand-on instructional demonstrations relating to topics presented in the lectures.

